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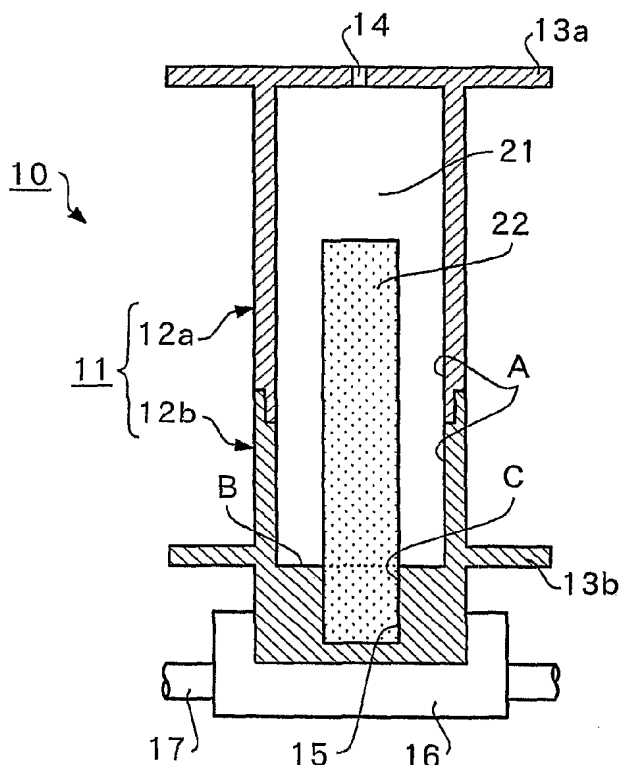
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(54) Title: VACUUM DEPOSITION METHOD AND SEALED-TYPE EVAPORATION SOURCE APPARATUS FOR VACUUM
DEPOSITION



(57) Abstract: A vacuum deposition method is provided. In the vacuum deposition for evaporating a sublimation evaporation material, the gas sealed-type heating container 11 has the blast aperture 14 and an area for evaporating the evaporation material by the radiation heat from the inner surface thereof. The holder 15 holds an evaporation material in a region in which the evaporation material does not evaluate due to the heat transferred from the heating container 11. Thus, the generated vapor is emitted from the blast aperture 14 into the deposition subject surface outside the container.



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